



Doc. 104

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ted A. Loxley  
Serial No. : 09/490,162  
Filed : January 22, 2000  
For: PROCESS AND APPARATUS FOR CLEANING SILICON WAFERS  
Examiner : V. Simkovic  
Group Art Unit : 2812

Box AF  
Assistant Commissioner for Patents  
Washington, D.C. 20231

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V. Vaxxall

AMENDMENT AFTER FINAL REJECTION

Please enter the following amendment to supplement the  
amendment filed December 5, 2001:

Page 1, cancel the first paragraph and substitute the  
following:

-- This application claims the benefit of my provisional  
application Serial No. 60/116,940 filed January 23, 1999. --

R E M A R K S

No fee is required for the present amendment. A check  
for \$180.00 is enclosed to cover the fee for the enclosed  
information disclosure statement.

Six patent references are cited in the enclosed Form  
PTO-1449 which may have some relevance. Copies of these  
references are enclosed for the file.

The patents to Uzoh ('619) and Glass ('964) disclose  
methods for use in integrated circuit fabrication wherein an  
ionic conductive aqueous electrolyte wets and covers the  
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substrate surface and wherein electrodes are employed to cause the flow of an ionic current to the substrate surface. In patent '619 the electric current is controlled to reduce the probable damage to the delicate microelectronic components at the wafer surface. In patent '964 the interfacial tension at the interface is controlled by applying an electrical potential difference of about 0.1 to about 1.0 volt (e.g., see pages 2, 9 and 13).

Entry of the amendment is requested.

Respectfully submitted,

*Vincent A. Greene*

Vincent A. Greene  
Attorney of Record  
Registration No. 17,389  
25931 Euclid Avenue, Suite 116  
Cleveland, Ohio 44132  
Telephone: (216) 481-7772

January 15, 2002